

In the Claims

Please cancel claim 25 without prejudice.

Please amend claims 20, 21, 22, 23, 24, 26, 27, 28, 29, 30, 31, 32, 33, 34, 35 and 36 as indicated in the attached Claims Listing.

A complete Claims Listing, showing all claims presently in the application and indicating the present status of each pending claim, is attached as required by 37 C.F.R. § 1.121(c).

Claims Listing

Claims 1-19 (Cancelled).

20. (Withdrawn and Currently Amended) [Optical] An optical assembly [having], comprising: a plurality of optical elements[[],] forming a projection objective or an illuminating system, [wherein] said plurality of optical elements including at least one optical element and a plurality of remaining optical elements, said at least one optical element being supported by [connected to] a structure which is dynamically decoupled from said remaining optical elements of said optical assembly, [as a result of which it] whereby, said at least one optical element is substantially dynamically decoupled from [[the]] said remaining optical elements of [[the]] optical assembly.

21. (Withdrawn and Currently Amended) [Optical] An optical assembly [according to] as claimed in Claim 20, wherein said optical assembly further comprises a housing, said housing having [provided in a housing of the optical assembly is] at least one opening through which said [dynamically decoupled] at least one optical element [[can be]] is connected to [[the]] said structure [dynamically decoupled from the optical assembly].

22. (Withdrawn and Currently Amended) [Optical] An optical assembly [according to] as claimed in Claim [[20]] 21, [wherein sensors are provided] further comprising a sensor for determining the position of said optical element relative to [[the]] at least one of: (i) said housing [or relative to the] and (ii) said remaining optical elements of [[the]] said optical assembly.

23. (Currently Amended) An apparatus, comprising: [an optical assembly and a feeder device] an interchange mechanism and an optical assembly[[];], said optical assembly having a [beam path] housing and having a plurality of optical elements [forming] arranged along a beam path to form a projection objective or an illuminating system, said plurality of optical elements including at least one selected optical element

and a plurality of remaining optical elements, said selected optical element being selectable from among a plurality of selectable optical elements available from said interchange mechanism, said [feeder device] interchange mechanism being operable to [interchangeably] insert said selected optical element into the beam path, and to remove said selected optical element from the beam path [at least one optical element], said selected optical element being inserted into an operating position in the beam path, said operating position being a position at which said selected optical element is separate from said interchange mechanism, said interchange mechanism being supported by a structure which is substantially dynamically decoupled from said housing and from said remaining optical elements arranged along the beam path [substantially dynamically decoupled from the remaining ones of said plurality of optical elements of the optical assembly] .

24. (Currently Amended) An apparatus according to Claim 23, wherein said interchange mechanism is located outside said housing and wherein said [optical assembly includes a] housing [having] includes an opening adapted to the dimensions of said [at least one] plurality of selectable optical elements [element] such that said at least one selected optical element [[being]] can be inserted into the beam path by way of said opening and removed from the beam path by way of said opening.

25. (Cancelled)

26. (Currently Amended) An apparatus according to Claim [[25,]] 23, wherein said interchange mechanism [further comprising] comprises a lifting device for lifting said at least one selected optical element, said at least one selected optical element being positioned and/or fixed in the beam path via said lifting device.

27. (Currently Amended) An apparatus according to Claim 26, wherein said lifting device is dynamically decoupled from [[the]] said optical assembly and is connected to [[the]] said structure which is substantially dynamically decoupled from [[the]] said optical assembly.

28. (Currently Amended) An apparatus according to Claim 23, [wherein said apparatus further comprises] further comprising a holding device which serves as a stop and/or for fixing said at least one selected optical element in the beam path.

29. (Currently Amended) An apparatus according to Claim 28, wherein [for the purpose of fixing said at least one optical element in the beam path,] said holding device is connected to one of said remaining ones of said plurality of optical elements.

30. (Currently Amended) An apparatus according to Claim 28, wherein said at least one selected optical element is fixed in the beam path by said holding device using a magnetic [forces] force.

31. (Currently Amended) An apparatus according to Claim 26, wherein spring elements are provided between said lifting device and said at least one selected optical element.

32. (Currently Amended) An apparatus according to Claim 26, wherein at least one of: (i) said [feeder device and/or] interchange mechanism and (ii) said lifting device, are [arranged] located outside [[the]] said housing of said optical assembly.

33. (Withdrawn and Currently Amended) An apparatus according to Claim ~~[[23]]~~ 21, wherein said dynamically decoupled optical element can be manipulated by means of actuators.

34. (Currently Amended) An apparatus according to Claim 23, wherein said at least one selected optical element ~~[[is]]~~ comprises a ~~[[diaphragm, in particular]]~~ a revolving disc diaphragm.

35. (Currently Amended) An apparatus [according to] as claimed in Claim 23, wherein said beam path comprises a beam path for EUV light [apparatus is used in a

projection exposure machine for microlithography in the field of EUVL for producing semiconductor components].

36. (Currently Amended) A projection exposure machine for semiconductor microlithography [in the EUVL field for producing semiconductor components], said projection exposure machine, comprising: [with the aid of] an apparatus in accordance with Claim 23 wherein, said beam path is a beam path for EUV light.